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and composition of the M-Si-N (M=alkali, alkaline earth or rare-earth metal) nitridosilicates†

On the relations between the bandgap, structure

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Relations between the bandgap and structural properties and composition of the M–Si–N nitridosilicates (M = alkali, alkaline earth or rare earth metal) have been obtained, using experimental data collected from literature; and qualitative models are presented to explain the observed trends. Compounds with a higher degree of condensation, *i.e.* a higher Si/N ratio, generally have longer M–N bonds and shorter Si–N bonds. The observations can be explained based on the effective charge of N, dependent on its coordination with Si (NSi_x). With increasing Si/N ratio the coordination number of N by Si increases, making the effective charge of the nitrogen atom less negative, resulting in a longer and less covalent M–N bond. This also shifts the N 2p levels down in energy, lowering the top of the valence band (mainly composed of N orbitals); while decreasing the Si–N distance shifts the bottom of the conduction band (mainly composed of Si and M orbitals) upward. Some nitridosilicates show deviations to the general trends, such as γ -Si₃N₄ and several Li-containing compounds. These deviations have been discussed and possible explanations have been given based on peculiarities in their structural characteristics

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1. Introduction

Nitridosilicates have gained a lot of attention over the last years, especially in luminescence research, owing to their large structural diversity and chemical and optical properties. These when doped with lanthanide ions such as Eu²⁺ or Ce³⁺, these compounds can show strong emission bands upon excitation with UV or blue light, with emission ranging from the blue to the red region. Some of these phosphors have shown high luminescence efficiency in combination with a good thermal and chemical stability, making them highly attractive for luminescence applications. Especially the Eu²⁺ doped nitridosilicates such as Sr₂Si₅N₈:Eu²⁺ have shown to be very promising and have been applied as conversion phosphors for phosphorconverted white LEDs (pc-wLEDs). Here, a UV or blue LED chip is combined with red- and green-emitting phosphors,

and in the case of a UV LED also blue-emitting phosphors, in

The nitridosilicates are compounds with the overall composition of $M_x Si_y N_z$ where M is an alkali (1+), alkaline earth (2+) or rare-earth (3+) metal ion or combination thereof. The structures generally consist of a framework of interconnected SiN_4 tetrahedra with the metal ions located in the cavities of the framework. This makes the nitridosilicates comparable to the oxosilicates, which consist of interconnected SiO_4 tetrahedra. However, in the oxosilicates the O atoms are usually one-fold or twofold coordinated by Si, with only a few compounds showing

order to produce white light with a high colour rendering index. Besides the use in white LEDs, nitridosilicate phosphors are also considered for other applications: as spectral conversion phosphors to enhance solar cell efficiency,8 as afterglow phosphors,9 and for LCD backlighting.10 In addition, the nitridosilicates have also attracted great interest outside the field of luminescence, mainly as ceramic materials¹¹ due to their chemical resistance, excellent mechanical properties at high temperature and low thermal expansion. It is noteworthy to mention that the nitridosilicates can be modified by replacing some of the Si by Al and N by O, forming silicon aluminium oxynitridosilicates, or sialons, 12,13 greatly enhancing the structural diversity. Examples of oxygen and/or aluminium containing nitridosilicate phosphors promising for white LED applications are Eu²⁺ doped Ca-α-sialon, 14,15 CaAlSiN₃, 16 β-sialon, 17 and SrSi₂O₂N₂. 18,19

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threefold coordination, as occurs in high-pressure phase stishovite (SiO₂).²⁰ In the nitridosilicates on the other hand, in addition to terminal (NSi₁) and bridging (NSi₂) nitrogen, the threefold coordination of N by Si (NSi₃) is much more common, and N can even be fourfold coordinated by Si (NSi₄). This allows for a much wider range of structures ranging from highly condensed Si₃N₄ with low M/Si ratio and high degree of condensation (Si/N ratio is 0.75), to Ca₄SiN₄ with a very low degree of condensation (Si/N ratio is 0.25) as a consequence of a high M/Si ratio. Such structural features strongly determine the chemical stability of the materials, showing a lower stability for compounds with a lower degree of cross-linking between SiN₄ tetrahedra.²¹ Nitridosilicates such as Ca₄SiN₄^{22,23} and Eu₂SiN₃²⁴ with a low degree of cross-linking are highly sensitive to water, while BaSi₇N₁₀²⁵ with a high degree of cross-linking is very stable against oxidation and not corroded by water.

In addition to stability variations among the nitridosilicate structures, there is also a large variation in their optical properties depending on the chemical composition (i.e. M/Si ratio). The bandgap of the $M_xSi_vN_z$ compounds can vary greatly from as small as 2.7 eV in Li₈SiN₄²⁶ to as large as 6.9 eV in LiSi₂N₃.^{27,28} This has its influence on the performance as a luminescent material when the nitridosilicate host lattice is doped with lanthanide ions. For example, the position of the lowest 5d level of Eu²⁺ with respect to the bottom of the conduction band strongly influences the efficiency and thermal stability of the Eu²⁺ 5d-4f emission. When positioned inside or close to the conduction band, auto-ionization or thermal ionization of the 5d electron to the conduction band may occur and the 5d-4f emission will be quenched.²⁹ Other examples are the position of the valence band with respect to the lanthanide 4f ground states that determines the energy of charge transfer transitions, ³⁰ and the position of the 4f ground state of the divalent ion with respect to the valence and conduction band that determines the valence stability of a divalent ion.³¹ These examples demonstrate the importance for the development of luminescent materials to know how the positions of the valence and conduction band of the phosphor host lattice are influenced by its composition and can be tuned.

This work presents the relations between the composition, structural properties and bandgap of the nitridosilicates and presents qualitative models that can explain the observed trends. For this we collect and analyse experimental data presented in literature on all $M_x Si_v N_z$ nitridosilicates where M is an alkali (1+), alkaline earth (2+) or rare earth (3+) metal or combination thereof. In the first part of the manuscript we discuss the structural characteristics of the nitridosilicates, such as bond lengths and coordination numbers, and relate it to the chemical compositions of the materials. A qualitative model is then developed to explain the influence that the Si/N ratio has on the bond lengths and coordination numbers. In the final part of the manuscript the relation between the bandgap and the structure and composition of the nitridosilicates is discussed. A second model is then developed to explain the influence of the Si/N ratio on the positions of the valence and conduction band.

The influence of chemical composition on crystal structure, bond lengths and bandgap

The nitridosilicates considered in this work (see Table 1) are all compounds with the general composition M,Si,N, where M is a monovalent alkali (A = Li⁺), divalent alkaline earth (AE = Mg²⁺, Ca^{2+} , Sr^{2+} , Ba^{2+}), or trivalent rare-earth (RE = Sc^{3+} , Y^{3+} , La^{3+} , or other trivalent lanthanide) metal ion, or combination thereof. M may also be a divalent rare earth (e.g. Eu^{2+}). Also included in this work is Ca_{0.8}Y_{1.2}Si₄N_{6.8}C_{0.2}, ³² because it only contains a small amount of carbon and is closely related to the other nitridosilicates. The structure is very similar to the pure nitride $(AE)(RE)Si_4N_7$ (AE = Ca, Sr, Ba; RE = Sc, Y, Lu, Yb) compounds, ³³ but is a disordered variant where nitrogen is partly replaced by carbon for charge compensation and a part of the Y3+ ions is present on the Ca²⁺ sites.³² The lithium and magnesium containing nitridosilicates such as Li₅SiN₃, Li₄Ca₃Si₂N₆, Li₄CaMg₂Si₂N₆, MgSiN₂ and SrMg₃SiN₄ have also been included, for the sake of comparison, even though it may be argued that some these compounds are not really nitridosilicates but nitrido-lithosilicates or nitrido-magnesosilicates because Li and Mg can be considered part of the nitridosilicate framework. This issue will be further discussed in this manuscript. The structural characteristics of all the nitridosilicates have been collected from experimental data from literature and are summarized in Table 1.

2.1 Crystal structure

Depending on the M/Si ratio of the nitridosilicates, different ways of N by Si coordination exist, as illustrated in Fig. 1. The non-metal silicon nitrides α -Si $_3N_4^{34,79}$ and β -Si $_3N_4^{35,80}$ both consist of a three-dimensional network of corner-sharing SiN₄ tetrahedra. All N atoms are coordinated by three Si atoms. As a result of its high degree of cross-linking between SiN4 tetrahedra, Si₃N₄ exhibits an outstanding chemical, thermal and mechanical stability. When introducing metals into the structure, Si-NSi2 bonds will be broken, reducing the degree of cross-linking between SiN₄ tetrahedra. As a result, compounds Ba), 46,48 LaSi $_3$ N $_5$ ^{56,81} and La $_3$ Si $_6$ N $_{11}$ ⁵⁶ have N atoms both threefold and twofold coordinated by Si. However, the SiN4 tetrahedra still form a three-dimensional network of corner-sharing or, as is the case for (AE)Si7N10, also edge-sharing tetrahedra. In compounds such as BaYbSi₄N₇⁸² and Ca₃Sm₃Si₉N₁₇⁷³ there is no threefold coordination, but unusual fourfold coordination of N by Si exists in addition to the twofold coordination. All N atoms are twofold coordinated by Si in α-CaSiN₂, SrSiN₂ and BaSiN₂. 44 In compounds with quite high M/Si ratios resulting in low Si/N ratios, N atoms can also be singly bonded by Si, as occurs partly in Eu₂SiN₃²⁴ and La₅Si₃N₉.⁵⁴ In these compounds the SiN₄ tetrahedra form non-branched (in Eu₂SiN₃) or branched (in La₅Si₃N₉) linear chains. In $(AE)_5Si_2N_6$ $(AE = Ca, Ba)^{23,43,51}$ and $Ca_4SiN_4^{23}$ the SiN₄ tetrahedra do not form interconnected networks anymore, but are isolated units (in Ca₄SiN₄) or form isolated Si₂N₆ pairs consisting of two edge-sharing tetrahedra (in (AE)₅Si₂N₆).

 Table 1
 Experimentally determined structural characteristics of the nitridosilicates $(M_x Si_y N_z)$ collected from literature

Compound	Space group	ICSD	Si-N network (CS = corner sharing, ES = edge sharing, 3D = 3-dimensional)	N by Si coordination $N^{[x]}$	Average M–N distance (Å)	Shortest Si–N distance ^a (Å)	Ref
α-Si ₃ N ₄	(159)	79 797	3D CS SiN ₄ network	$N_{[3]}^{[3]}$	_	1.673	34
β -Si ₃ N ₄	(173)	8263	3D CS SiN ₄ network	$N_{[3]}^{[3]}$	_	1.704	35
γ-Si ₃ N ₄	(227)	97 566	3D ES/CS SiN ₄ /SiN ₆ network	$N_{L}^{[4]}$	_	1.853	36
$\text{Li}_{21}\text{Si}_{3}\text{N}_{11}$	(79)	191 135	b b	b b	2.111	1.656	37
Li ₅ SiN ₃	(206)	25582			2.084	1.910	38
Li ₂ SiN ₂	(61)	420 126	3D CS SiN ₄ network	$N^{[2]}$	2.160	1.728	39
LiSi ₂ N ₃	(36)	98 524	3D CS SiN ₄ network	$1N^{[2]}:2N^{[3]}$	2.263	1.681	40
MgSiN ₂	(33)	90731	3D CS SiN ₄ network	N ^[2]	2.249	1.732	41
Mg ₂ Si ₅ N ₈	(9)		3D CS SiN ₄ network	$1N^{[2]}:1N^{[3]}$ $N^{[1]}$	2.305	1.660	42
Ca ₄ SiN ₄	(14)	250 872	Isolated SiN ₄ tetrahedrons	$N^{[1]}$ $2N^{[1]}:1N^{[2]}$	2.522	1.767	23
α-Ca ₅ Si ₂ N ₆	(15)	414 462	Isolated pairs of ES SiN ₄	2N ^[1] :1N ^[2]	2.575	1.713	43
β-Ca ₅ Si ₂ N ₆	(12)	250 873	Isolated pairs of ES SiN ₄	N ^[2]	2.578	1.735	23
α-CaSiN ₂ Ca ₁₆ Si ₁₇ N ₃₄ ^c	(61) (216)	170 267 248 945	3D CS SiN ₄ network 3D CS SiN ₄ network	2N ^[1] :14N ^[2] :1N ^[4]	2.583 2.536	1.729	44 45
	(216) (9)	79 070	3D CS SiN ₄ network 3D CS SiN ₄ network	$1N^{[2]}:1N^{[3]}$	2.646	1.645	
Ca ₂ Si ₅ N ₈		79070	3D CS SiN ₄ network 3D CS SiN ₄ network	$1N^{[2]}:1N^{[3]}$	2.730	1.671 1.618	46 42
β-Ca ₂ Si ₅ N ₈ HP-Ca ₂ Si ₅ N ₈	(4) (61)	419 318	3D CS SiN ₄ network 3D CS SiN ₄ network	$1N^{[2]}:1N^{[3]}$	2.577	1.664	47
	(61) (14)	170 270	3D CS/ES SiN ₄ network 3D CS/ES SiN ₄ network	$N^{[2]}$	2.859	1.711	44
SrSiN ₂	(31)	401 500	3D CS SiN ₄ network	1N ^[2] :1N ^[3]	2.949		
Sr ₂ Si ₅ N ₈ SrSi ₇ N ₁₀	(31)	154 166	3D CS SiN ₄ network 3D CS and ES SiN ₄ network	$1N^{[2]}:4N^{[3]}$	3.069	1.675 1.683	48 49
SrSi ₆ N ₈	(44)	319 265	3D CS SiN ₄ network (Si–Si bonds)	1N .4N 1N ^[2] :3N ^[3]	3.028	1.691	50
Ba ₅ Si ₂ N ₆	(19)	81 570	Isolated pairs of ES SiN ₄	2N ^[1] :1N ^[2]	2.862	1.747	51
BaSiN ₂	(64)	170 268	3D CS/ES SiN ₄ network	$\mathbf{N}^{[2]}$	2.991	1.719	44
Ba ₂ Si ₅ N ₈	(31)	401 501	3D CS SiN ₄ network	1N ^[2] :1N ^[3]	2.999	1.686	48
BaSi ₇ N ₁₀	(7)	405 772	3D CS and ES SiN ₄ network	$1N^{[2]}:4N^{[3]}$	3.269	1.683	25
BaSi ₆ N ₈	(44)	417 444	3D CS SiN ₄ network (Si–Si bonds)	1N ^[2] :3N ^[3]	3.062	1.667	52
Eu ₂ Si ₅ N ₈	(31)	59 257	3D CS SiN ₄ network	1N ^[2] :1N ^[3]	2.894	1.681	53
$La_5Si_3N_9$	(64)	419 064	Branched chains of CS SiN ₄	$2N^{[1]}:1N^{[2]}$	2.711	1.564	54
$La_3Si_6N_{11}$	(100)	248 709	3D CS SiN ₄ network	$9N^{[2]}:2N^{[3]}$	2.676	1.711	55
LaSi ₃ N ₅	(19)	130 022	3D CS SiN ₄ network	$3N^{[2]}:2N^{[3]}$	2.802	1.690	56
Ce ₅ Si ₃ N ₉	(64)	419 063	Branched chains of CS SiN ₄	$2N^{[1]}:1N^{[2]}$	2.685	1.725	54
Ce ₇ Si ₆ N ₁₅ (tricl.)	(2)	420 199	3D CS SiN ₄ network	$2N^{[1]} \cdot 5N^{[2]}$	2.772	1.705	57
Ce ₇ Si ₆ N ₁₅ (trig.)	(148)	420 200	3D CS SiN ₄ network	2N ^[1] :5N ^[2]	2.770	1.625	57
$Ce_3Si_6N_{11}$	(100)	237 444	3D CS SiN ₄ network	$9N^{[2]}:2N^{[3]}$	2.661	1.725	58
CeSi ₃ N ₅	(19)	402 910	3D CS SiN ₄ network	$3N^{[2]}:2N^{[3]}$	2.783	1.686	56
Pr ₅ Si ₃ N ₉	(64)	260 288	Branched chains of CS SiN ₄	$2N^{[1]}:1N^{[2]}$	2.672	1.719	59
$Pr_7Si_6N_{15}$	(2)	420201	3D CS SiN ₄ network	$2N^{[1]}:5N^{[2]}$	2.762	1.693	57
$Pr_3Si_6N_{11}$	(100)	402178	3D CS SiN ₄ network	$9N^{[2]}:2N^{[3]}$	2.646	1.703	60
$Sm_3Si_6N_{11}$	(100)	80 183	3D CS SiN ₄ network	$9N^{[2]}:2N^{[3]}$	2.618	1.697	56
Li ₄ Ca ₃ Si ₂ N ₆	(12)	420675	Isolated pairs of ES SiN ₄ ^d	$2N^{[1]}:1N^{[2]}$	2.596 (Ca)	1.711	61
Li ₄ Sr ₃ Si ₂ N ₆	(12)	421259	Isolated pairs of ES SiN ₄ ^d	$2N_{[1]}^{[1]}:1N_{[2]}^{[2]}$	2.735 (Sr)	1.735	61
Li ₄ Ca ₂ MgSi ₂ N ₆	(12)	427077	Isolated pairs of ES SiN ₄ ^d	$2N^{[1]}:1N^{[2]}$	2.482 (Ca)	1.743	62
Li ₂ Ca ₂ Mg ₂ Si ₂ N ₆	(12)	427078	Isolated pairs of ES SiN ₄ ^d	$2N_{[1]}^{[1]}:1N_{[2]}^{[2]}$	2.588 (Ca)	1.720	62
Li ₂ Ca ₃ MgSi ₂ N ₆	(12)		Isolated pairs of ES SiN ₄ ^d	$2N_{[0]}^{[1]}:1N_{[1]}^{[2]}$	2.554 (Ca)	1.720	63
$\text{Li}_2\text{Sr}_4[\text{Si}_2\text{N}_5]\text{N}$	(119)	422596	Layered CS SiN ₄ network	$1N_{[1]}^{[0]}:2N_{[2]}^{[1]}:3N_{[2]}^{[2]}$	2.694 (Sr)	1.751	64
LiCa ₃ Si ₂ N ₅	(15)	420676	Double chain of ES/CS SiN ₄	$2N^{[1]}:1N^{[2]}$	2.540 (Ca)	1.726	65
Li ₂ CaSi ₂ N ₄	(205)	421548	3D CS SiN ₄ network	$N^{[2]}_{-}$	2.528 (Ca)	1.714	66
Li ₂ SrSi ₂ N ₄	(205)	421 549	3D CS SiN ₄ network	N ^[2]	2.699 (Sr)	1.738	66
Li ₅ La ₅ Si ₄ N ₁₂	(117)	421 528	Non-br. chains CS SiN ₄	2N ^[1] :1N ^[2]	2.609 (La)	1.740	67
Li ₅ Ce ₅ Si ₄ N ₁₂	(117)	421 527	Non-br. chains CS SiN ₄	$2N^{[1]}:1N^{[2]} \ N^{[1]}$	2.605 (Ce)	1.709	67
CaMg ₃ SiN ₄	(88)	427 074	Isolated SiN ₄ tetrahedrons ^d	$N^{[1]}$ $N^{[1]}$	2.638 (Ca)	1.763	68
SrMg ₃ SiN ₄	(88)	427 076	Isolated SiN ₄ tetrahedrons ^d	$N^{[1]}$ $N^{[1]}$	2.802 (Sr)	1.791	68
EuMg ₃ SiN ₄	(88)	427 075	Isolated SiN ₄ tetrahedrons ^a	Nu	2.680 (Eu)	1.757	68
BaMg ₃ SiN ₄	(2)	428 510	3D CS (Si,Mg)N ₄ network		2.953 (Ba)	1.892	69
Ba ₄ MgSi ₂ N ₆	(70-2)	187 335	Isolated pairs of ES SiN ₄	2N ^[1] :1N ^[2]	2.953 (Ba)	1.739	70
Ba ₃ Ca ₂ Si ₂ N ₆	(15)	187 336	Isolated pairs of ES SiN ₄	$2N^{[1]}:1N^{[2]}$	2.910 (Ba)	1.730	70
Ba _{1.6} Sr _{3.4} Si ₂ N ₆	(15)	187 337	Isolated pairs of ES SiN ₄	$2N^{[1]}:1N^{[2]}$		1.718	70 71
CaLaSiN ₃ Eu ₂ SiN ₃	(64) (64)	420 679	Non-branched chains CS SiN₄ Non-branched chains CS SiN₄	2N ^[1] :1N ^[2]	2.764 (Eu ²⁺)	1.731	71 24
$Ba_2Nd_7Si_{11}N_{23}$	(64)	420 679	3D CS SiN ₄ zeolite network	2N ^[1] :21N ^[2]	3.164 (Ba)	1.685	72
$Ca_3Sm_3Si_9N_{17}$	(215)	407 202	3D CS SiN ₄ zeonte network 3D CS SiN ₄ network	16N ^[2] :1N ^[4]	e (Da)	1.696	73
Ca ₃ Sin ₃ Si ₉ N ₁₇ Ca ₃ Yb ₃ Si ₉ N ₁₇	(215) (215)	421 645	3D CS SiN ₄ network 3D CS SiN ₄ network	16N ^[2] :1N ^[4]	e	1.687	73 73
$\text{Ba}_{1.5}\text{Eu}_{1.5}\text{YbSi}_{6}\text{N}_{11}$	(198)	407 300	3D CS SiN ₄ network 3D CS SiN ₄ network	$9N^{[2]}:2N^{[3]}$	3.012 (Ba)	1.701	73 74
SrScSi ₄ N ₇	(186)	189 117	3D CS SiN ₄ network 3D CS SiN ₄ network	6N ^[2] :1N ^[4]	2.957 (Sr) ^f	1.688 ^f	74 75
0100014117	(186)	152 975	3D CS SiN ₄ network 3D CS SiN ₄ network	$6N^{[2]}:1N^{[4]}$	e (D1)	1.709	32
CaYSi ₄ N ₋ ^g		1043/3	OD OD DII 14 HOUNDIN	011 111		1./ 0./	34
	1 1			$6N^{[2]} \cdot 1N^{[4]}$	3.012 (Sr)	1 699	76
CaYSi ₄ N ₇ ^g SrYSi ₄ N ₇ BaYSi ₄ N ₇	(186) (186)	150 459 98 276	3D CS SiN ₄ network 3D CS SiN ₄ network	6N ^[2] :1N ^[4] 6N ^[2] :1N ^[4]	3.012 (Sr) 3.014 (Ba)	1.699 1.701	76 77

Table 1 (continued)

Compound	Space group	ICSD	Si-N network (CS = corner sharing, ES = edge sharing, 3D = 3-dimensional)	N by Si coordination $N^{[x]}$	Average M–N distance (Å)	Shortest Si–N distance ^a (Å)	Ref.
SrYbSi ₄ N ₇ EuYbSi ₄ N ₇	(186) (186)	405 625 592 58	3D CS SiN ₄ network 3D CS SiN ₄ network	6N ^[2] :1N ^[4] 6N ^[2] :1N ^[4]	2.996 (Sr) 2.993 (Eu)	1.708 1.713	78 53
BaYbSi ₄ N ₇	(186)	405 194	3D CS SiN ₄ network 3D CS SiN ₄ network	$6N^{[2]}:1N^{[4]}$	3.017 (Ba)	1.717	78

^a If there are multiple Si sites with different Si-N distances in a structure, the average is taken of the shortest Si-N distance of each site. ^b Li₂₁Si₃N₁₁ and Li₂SiN₃ both crystallize in an anti-fluorite (Li,Si)₂N structure with N 8-fold coordinated by Si and Li. c Ca₁₆Si₁₇N₃₄ is also known as cubic-CaSiN₂. d Structures may also be considered a 3D network of corner-sharing and edge-sharing SiN₄ and LiN₄ and/or MgN₄ tetrahedra. Compound contains mixed Sr/Ba, Ca/Sm, Ca/Yb or Ca/Y sites. ^f Distances based on a structure doped with 5% Eu. ^g CaYSi₄N₇ is actually Ca_{0.8}Y_{1.2}Si₄N_{6.8}C_{0.2}.

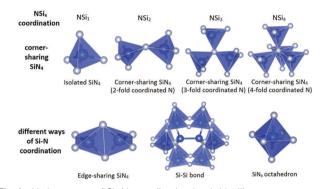


Fig. 1 Various ways of Si-N coordination in nitridosilicates

In all the previously mentioned cases, the Si and N atoms are present in SiN₄ tetrahedra. As a consequence, there is a direct relation between the degree of condensation κ (here defined as the Si/N ratio) and the average coordination number x of nitrogen by silicon (NSi_x), with $x = 4 \times \kappa$, as is shown in Fig. 2. There are a just few nitridosilicates in which not all Si and N atoms are present in SiN₄ tetrahedra and the relation $x = 4 \times \kappa$ is not followed: γ -Si₃N₄ and (AE)Si₆N₈ (AE = Sr, Ba), which are indicated with blue squares in Fig. 2. In γ-Si₃N₄ with cubic spinel structure83 all N atoms are fourfold coordinated by Si and SiN₆ octahedra exist in addition to SiN₄ tetrahedra. In $(AE)Si_6N_8$ $(AE = Sr, Ba)^{50,52}$ $N_3Si-SiN_3$ entities are present in which two Si atoms are directly bonded to each other.

The M cations are the positive counterions of the negative nitridosilicate framework and are located in the cavities of the network. They are usually coordinated by six or more N atoms. However, if the metal ion is relatively small, as is the case for Mg^{2+} and Li⁺, they can also form TN_4 (T = Mg, Li) tetrahedrons similar to the SiN₄ tetrahedrons. It may then be more appropriate to consider them part of the framework instead of as counterions. This is for example the case in Li₅SiN₃ with antifluorite structure where Si and Li are located on mixed sites forming (Si,Li)N₄ tetrahedrons.^{37,38} In several other Li and Mg containing nitridosilicates the situation is however less obvious. Li₄Ca₃Si₂N₆ consists of SiN₄ and LiN₄ tetrahedra with octahedrally coordinated Ca²⁺ ions in between, so Si and Li can be considered part of the 3D framework and the compound could be written as Ca₃[Li₄Si₂N₆].^{61,62} However, for the same structure one of the Ca2+ ions can be replaced by two Li+ ions, while at the same time 4 Li⁺ ions are replaced by 2 Mg²⁺ ions resulting in Li₂Ca₂[Mg₂Si₂N₆] in which tetrahedrally coordinated

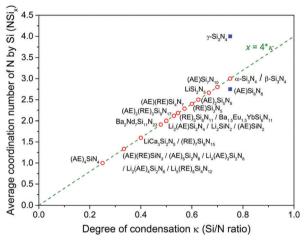


Fig. 2 Average coordination number x of N by Si (NSi_x) versus the degree of condensation κ (Si/N ratio) of the nitridosilicates. The green dashed line indicates the linear relationship $x = 4 \times \kappa$. Compounds that follow this relation are indicated by open red circles, compounds that do not are indicated by solid blue squares.

Mg is now part of the framework and Li⁺ is now a counterion forming [Li₂]N₆ octahedra. 62 Starting form Ca₃[Li₄Si₂N₆] the Mg can also be positioned on a Ca site, while the remaining Ca²⁺ ions switch positions with the Li⁺ ions on the [Li₂]N₆ positions, forming Ca2Mg[Li4Si2N6] in which now Li is part of the framework in a tetrahedral coordination and Mg^{2+} is a counterion in a fourfold planar rectangular coordination.⁶²

However, because Li⁺ and Mg²⁺ have a larger ionic radius, a lower electronegativity, and a lower oxidation number than Si⁴⁺, the influence of Li⁺ and Mg²⁺ on parameters like bond lengths and bandgap will be different. Consequently, it is not appropriate to simply add up the Si, Li and Mg atoms and use the (Si + Mg + Li)/N ratio as the principal parameter. Therefore, the Si/N ratio is used as the principal parameter in this manuscript, even when Mg and/or Li may be considered part of the crosslinking framework. As a result, a compound like Ba[Mg₃SiN₄] that is reported⁶⁹ to have a degree of condensation of 1 based on its (Mg + Si)/N ratio, is listed as a compound with a Si/N ratio of 0.25 in this work.

2.2 Bond lengths

Since N is in the -III oxidation state and Si in the +IV oxidation state, the effective charge of the N atom will be zero if it is threefold coordinated by tetrahedrally coordinated Si atoms (NSi3).

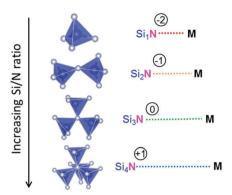


Fig. 3 Increase of the M-N bond length with increasing N by Si coordination.

In twofold coordination (NSi₂), the N atom is under-bonded, causing it to be effectively -1 negatively charged. This will therefore result in a stronger, more covalent interaction between N and the positively charged metal ion M in the structure. It can therefore be expected that the M-N bond will be shorter when N is in NSi₂ coordination than when N is in the ideal NSi₃ coordination. If the N atom is only terminally coordinated by Si (NSi₁) this effect will become more pronounced. Vice versa, a less covalent interaction and longer M-N bond can be expected if the N atom is over-bonded in a fourfold coordination by Si. This means that one may expect an increase of the average M-N distance with increasing Si/N ratio, as schematically illustrated in Fig. 3.

As expected, a larger M-N distance with increasing Si/N ratio is indeed the trend that can be qualitatively observed from the experimental data collected from literature (Table 1), and shown in Fig. 4. For the Ca, Sr, Ba and La sites the average distance to nitrogen tends to increase with increasing Si/N ratio in correspondence with a more positive effective charge for N. It should be noted here that, even though a linear fit through the data is presented, this does not imply that the relation between Si/N ratio and M-N distance should be linear. The purpose of the linear fit is to show that there seems to be a general trend showing an increase of M-N distance with increasing Si/N ratio, but several secondary effects might be present that cause an increased scattering of the data. Nevertheless, the deviation from the general trend is in most compounds less than 0.05 Å. The strongest increase of M-N distance with increasing Si/N ratio is observed for M = Sr, while the increase is weakest for M = Ca. The reason for the surprising order Sr-N > Ba-N >Ca-N (while in terms of size and atomic number Ba > Sr > Ca) is unclear and further studies would be necessary to clarify its cause. It might be a consequence of scattering of the data due to secondary effects as some data points have a relatively strong influence on the steepness of the slope.

For the Ca sites, the increase of the Ca-N distance with increasing Si/N ratio is rather limited with only about 0.1 Å difference between Ca₄SiN₄ and Ca₂Si₅N₈. This makes the increase smaller than the scattering of the data. For example, among the compounds with a Si/N ratio of 1/3, Li₄Ca₃Si₂N₆ has an almost 0.2 Å larger average Ca-N bond length than Li₄Ca₂MgSi₂N₆. As was discussed above Li₄Ca₂MgSi₂N₆ is homeotypic to Li₄Ca₃Si₂N₆ but Ca²⁺ ions have been partly replaced by Mg²⁺ ions and the

remaining Ca2+ ions have switched places with the Li+ ions, which can explain the relatively short Ca-N bond length in Li₄Ca₂MgSi₂N₆. For the Sr sites the absolute scattering of the data is similar as for the Ca sites. However, among the Sr sites there is a large increase of the Sr-N distance with increasing degree of condensation, making the scattering relatively small. For the Ba sites the observed dependence on Si/N ratio is also strong, but the deviation from the general trend is quite large for BaSi₇N₁₀ and Ba₂Nd₇Si₁₁N₂₃, having relatively large Ba-N distances. This may be due to the large coordination numbers for Ba in these compounds. In BaSi₇N₁₀ the coordination number is 13,²⁵ while in Ba₂Nd₇-Si₁₁N₂₃, which has an unusual zeolite-analogous structure, ⁷² the coordination number of some of the Ba atoms goes up to even 16.

Some scattering in the data of Fig. 4 may also be due to the fact that the Si/N ratio, which basically is a measure for the average N coordination number (see Fig. 2), may not exactly represent the actual N by Si coordination number of the N atoms surrounding the metal ion. In BaYSi₄N₇ for example, the N atoms have an average coordination number of 2.29 because the ratio of twofold/fourfold coordinated N atoms is 6/1. However, the N atoms surrounding Ba have an average coordination number of 2 as the fourfold coordinated N atoms are far away from and not coordinated to Ba. In addition, the scattering of the data in Fig. 4 may be enhanced due to the presence of different types of metal ions M within one compound.

While the M-N bond lengths increase with increasing degree of condensation, the Si-N bond lengths tend to decrease with increasing degree of condensation, as has previously been observed by Schnick et al. 12,84 This can also be observed from the data shown in Fig. 5a: the average Si-N distance is relatively large in for example Ca₄SiN₄ (1.791 Å) with very low degree of condensation, while relatively small in SrSi₇N₁₀ (1.731 Å) with a very high degree of condensation.

If the shortest Si-N distance is plotted versus the Si/N ratio (Fig. 5b) instead of the average Si-N distance (Fig. 5a), a similar trend is observed. The correlation of the data is then somewhat stronger, considering that the Pearson correlation coefficient changes from -0.53 for the fit of the average Si-N distance versus Si/N ratio to -0.67 for fit of the shortest Si-N distance versus Si/N ratio. Note that the slope of the trend line in Fig. 5b (shortest Si-N distance) is also steeper than in Fig. 5a (average Si-N distance).

A few compounds do not follow the general trend in Fig. 5a and b and have either a relatively large or relatively small shortest Si–N bond. Among them is γ -Si₃N₄ with a relatively large Si–N distance of 1.853 Å. Note that this is the only compound listed in which SiN₆ octahedra are present in addition to SiN₄ tetrahedra. Two Li compounds also deviate with Li₅SiN₃ having a much larger Si-N distance and Li₂₁Si₃N₁₁ having a relatively small distance. Both compounds crystallize in distorted antifluorite structures and both are very Li rich, with the Li and Si atoms present in TN₄ (T = Li, Si) tetrahedra. So, based on their crystal structures both Li₅SiN₃ and Li₂₁Si₃N₁₁ are not really nitridosilicates composed of cross-linked tetrahedra such as the other compounds. It has been reported37 that in Li21Si3N11 the Si is mainly present on the smallest TN₄ site (because Si⁴⁺ is smaller than Li⁺), resulting in a small Si-N bond length. In Li₅SiN₃ on the other hand,

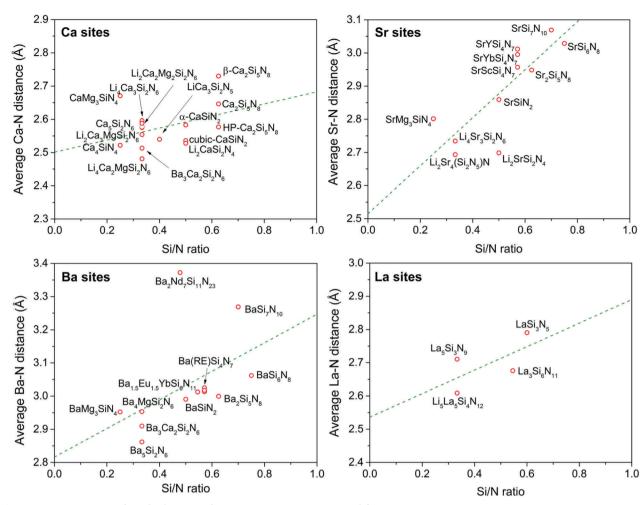


Fig. 4 Average M–N distance (M = Ca, Sr, Ba or La) in the nitridosilicates versus the Si/N ratio. The green dashed line represents a trend line obtained by a linear fit through the data points.

Si occupies a mixed Si/Li site making the Si-N distance actually a significantly larger (Si,Li)-N distance. Something similar also happens in BaMg₃SiN₄ with mixed Mg/Si sites and thus a large shortest (Mg,Si)-N distance (1.892 Å) since Mg²⁺ is larger than Si⁴⁺. The average (Mg,Si)-N distance in BaMg₃SiN₄ is also very large (2.030 Å) and falls outside the plotted range of Fig. 5a. In the other (AE)Mg₃SiN₄ compounds (AE = Ca, Sr, Eu) the Mg and Si sites are not mixed and the Si-N bond lengths are as expected for compounds with low Si/N ratio and in the same range as in Ca₄SiN₄. The very small shortest Si-N distance of 1.564 Å reported⁵⁴ for La₅Si₃N₉ seems to be not reliable, because for Ce₅Si₃N₉ and Pr₅Si₃N₉, that both crystallize in the same crystal structure as La₅Si₃N₉, the reported^{54,59} shortest Si-N distances are much larger (1.725 Å for Ce₅Si₃N₉ and 1.719 Å for Pr₅Si₃N₉) and fall in line with the trend observed in Fig. 5b. Hence that the La³⁺ ion is similar in size as the Ce³⁺ and Pr³⁺ ions. Note that the average Si-N distance in La₅Si₃N₉ is not an exception, but in range with the other compounds.

2.3 Bandgap

The bandgaps of the $M_xSi_vN_z$ compounds, listed in Table 2, have been derived from experimental data from literature. In cases the electrical bandgap E_{VC} , i.e. the energy between the top of the valence band and the bottom of the conduction band, has not been reported, E_{VC} is estimated from the exciton creation energy $E_{\rm ex}^{85,86}$ or the optical bandgap $E_{\rm opt}$. For this, absorption or reflectance spectra from undoped compounds and photoluminescence excitation spectra of low concentrated Eu²⁺ or Ce³⁺ doped compounds have been used. For several compounds, the bandgap has been calculated in literature using DFT calculations. These computationally determined bandgaps have not been taken into account as these calculations often tend to underestimate the real value of the bandgap, making comparison with experimentally determined values of other compounds not reliable. More information on the derivation of the bandgap from literature data can be found in the ESI.†

Among the nitridosilicates listed in Table 2, Li₂SiN₂ has the largest bandgap (>6.9 eV) and Li₈SiN₄ has the smallest bandgap (2.7 eV). In general the bandgap increases with increasing Si/N ratio, as shown in Fig. 6. This is in accordance with what was previously predicted by Fang et al. 116 using first principle calculations for the barium nitridosilicates: the bandgap increases with increasing degree of cross-linking between SiN4 tetrahedra in

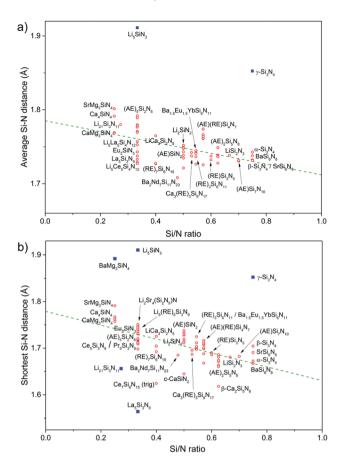


Fig. 5 (a) Average and (b) shortest Si-N distance in the nitridosilicates versus the Si/N ratio. The green dashed line represents a trend line obtained by a linear fit through the open red circular data points. The solid blue squared data points are exceptions not included in the fit. The average Si-N distance is defined as the average of all Si-N distances from all SiN₄ tetrahedra; the shortest Si-N distance is defined as the average of all shortest Si-N distances from all SiN₄ tetrahedra.

the order $Ba_5Si_2N_6 < Ba_2Si_5N_8 < BaSi_7N_{10} < \beta\text{-S}i_3N_4$. In the previous section it was explained that with increasing degree of condensation (Si/N ratio) the N atom will get a less negative effective charge. This less negative effective charge will result in a downward shift in energy of the N 2p levels, and because the top of the valence band consists mainly of N 2p levels, this will make the bandgap larger. This is also in line with the calculation by Fang et al., 116 showing a downward shift of the N 2p levels when going from singly coordinated N atoms towards N atoms coordinated by 4 Si atoms.

The increase of the bandgap with increasing degree of condensation is not only caused by a shift of the top of the valence band to lower energy, but should also be partly due to a shift of the bottom of the conduction band to higher energy (with respect to the vacuum level). As was discussed above, the Si-N bond length decreases with increasing Si/N ratio (Fig. 5). The shorter, and therefore stronger bond will give a larger splitting between the bonding orbitals at the top of the valence band (mainly N orbitals) and antibonding orbitals at the bottom of the conduction band (Si orbitals). This will result in a shift of the bottom of the conduction band to higher energy, next to a

Table 2 Bandgap E_{VC} of the nitridosilicates $(M_xSi_vN_z)$. The third column specifies the type of experiment from which the bandgap was derived (diffuse reflectance (DR), soft X-rays, optical absorption (ABS), photoluminescence excitation (PLE)) and the corresponding references. See the ESI for more details

Compound	$E_{\rm VC}$ (eV)	Ref.
α-Si ₃ N ₄	5 . 9	DR ⁸⁷
γ -Si ₃ N ₄	5.1	X-rays, 88 PLE 89
Li ₈ SiN ₄	2.7	ABS ²⁶
Li ₅ SiN ₃	2.8	ABS^{90}
LiSi ₂ N ₃	6.9	DR , 28 PLE^{27}
Li_2SiN_2	>6.9	$\mathrm{DR}^{\mathrm{91}}$
$MgSiN_2$	5.5	DR, ^{92,93} X-rays ⁹⁴
α -CaSiN ₂	5.0	$DR,^{95,96} PLE^{95}$
$\operatorname{Ca}_{16}\operatorname{Si}_{17}\operatorname{N}_{34}{}^a$	4.7	$ABS_{\bullet}^{97} DR^{97,98}$
$Ca_2Si_5N_8$	5.2	$DR,^{99} PLE^{99,100}$
$SrSiN_2$	5.0	ABS, 93 DR, 93,101 PLE 93,101
$Sr_2Si_5N_8$	5.1	$DR^{99,102} PLE^{99,100}$
SrSi ₆ N ₈	3.7	$DR.^{103} PLE^{104}$
BaSiN ₂	4.9	ABS. 93 DR. 93 PLE 93
$Ba_2Si_5N_8$	5.1	ABS, 105 DR, 99 PLE 99,100
BaSi ₇ N ₁₀	5.8	$DR_{106}^{106} PLE^{107}$
LaSi ₃ N ₅	5.0	ABS, 108 DR, 109 PLE 109,110
CaMg ₃ SiN ₄	4.1	PLE^{68}
SrMg ₃ SiN ₄	4.1	DR^{68}
BaMg ₃ SiN ₄	4.1	DR^{69}
$\text{Li}_2\text{Ca}_2\text{Mg}_2\text{Si}_2\text{N}_6$	4.8	DR^{111}
Li ₄ Ca ₃ Si ₂ N ₆	4.1	ABS, 112 DR, 112 PLE 112
CaLaSiN ₃	3.1	DR^{113}
CaYSi ₄ N ₇ ^b	5.2	DR^{114}
SrYSi ₄ N ₇	5.2	DP ^{76,77,114} DI E ⁷⁶
BaYSi ₄ N ₇	5.2	$DR^{77,114,115}$

^a Ca₁₆Si₁₇N₃₄ is also known as cubic-CaSiN₂. ^b CaYSi₄N₇ is actually $Ca_{0.8}Y_{1.2}Si_4N_{6.8}C_{0.2}$.

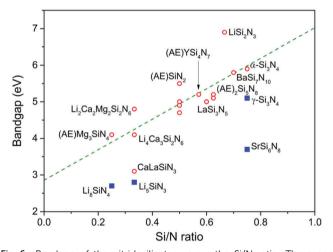


Fig. 6 Bandgap of the nitridosilicates versus the Si/N ratio. The green dashed line represents a trend line obtained by a linear fit through the red circular data points; the blue squared data points are exceptions not included for the fit

shift of the top of the valence band to lower energy. Based on analysis of the thermal quenching behaviour of the Eu2+ and Ce³⁺ 5d–4f emission in doped nitridosilicates it can be argued that the bottom of the conduction band should indeed shift upwards in energy with increasing degree of condensation, as will be explained in more detail in our next paper. So the

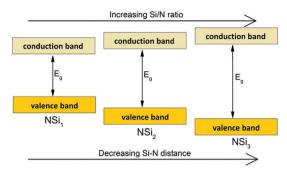


Fig. 7 Schematic diagram, showing the influence of the degree of condensation (Si/N ratio) on the positions of the valence and conduction bands and the size of the bandgap E_{α}

increasing bandgap of the nitridosilicates with increasing degree of condensation (increasing Si/N ratio) is the consequence of the combined effect of the downward shift of the valence band and the upward shift of the conduction band as illustrated in Fig. 7. It should be noted here that this model does not take into account that the bottom of the conduction band may not only consist of Si orbitals but may also consist of M orbitals. For example, calculations on the electronic structure of LaSi₃N₅ and La₃Si₆N₁₁ show that the bottom of the conduction band of these compounds contains La 4f and 5d states. 117 Nevertheless, the calculations still show that La₃Si₆N₁₁, which has a lower Si/N ratio, has a smaller bandgap than LaSi₃N₅ and a conduction band minimum at lower energy. The smaller bandgap may seem contradictory to the shorter La-N distance in La₃Si₆N₁₁, but could be explained by the larger crystal field splitting and centroid shift of the 5d levels in La₃Si₆N₁₁ as compared to LaSi₃N₅, lowering the bottom of the conduction band.

The bandgaps of $SrSi_6N_8$ (about 3.7 eV) and γ - Si_3N_4 (about 5.1 eV) are small considering their high Si/N ratios and deviate from the trend established for the other nitridosilicates. As already mentioned, in γ-Si₃N₄ not all Si atoms are tetrahedrally coordinated by N. The presence of SiN₆ octahedra causes a lowering of the Si 3s states at the bottom of the conduction band. 116 The smaller bandgap is also in line with the larger Si-N bond length in γ-Si₃N₄ as compared to those bonds in α -Si₃N₄ and β -Si₃N₄ (Fig. 5). In SrSi₆N₈ as another exception not all Si atoms are tetrahedrally coordinated by N, as part of the Si atoms form Si-Si bonds. The Si-Si bonds create an empty σ^* anti-bonding state forming the bottom of the conduction band, resulting in the smaller bandgap. 118 Therefore it is likely that BaSi₆N₈, in which also Si-Si bonds are present, has a relatively small bandgap as well, but to our knowledge its bandgap has not yet been experimentally determined.

For Li₂SiN₂ the exact value of the bandgap is unknown, but it should be larger than 6.9 eV since it has a high reflectivity down to 200 nm radiation. 91 The bandgap is thus very large considering that the Si/N ratio is only 0.5 and in the same range with that of LiSi₂N₃, which also has a relatively large bandgap. Such large bandgaps can be attributed to the presence of Li. As Li⁺ ions are relatively small, the Li-N bond is short compared to the M-N bond in other nitridosilicates. Instead of considering

the coordination number of N based on the number of Si atoms around it, also the coordinating Li atoms should therefore be taken into account. This increases the N(Si,Li)_x coordination number to about 4 in LiSi₂N₃ and even to 6 in Li₂SiN₂, meaning that the effective charge around N becomes more positive, the top of the valence band shifts downwards and the bandgap becomes large. Note that the same reasoning does not apply for Li₅SiN₃ which has a very small bandgap. The Si atoms are here located on the large Li sites, making the (Si,Li)-N bonds much longer (see Fig. 5) and weaker than in LiSi₂N₃ and Li₂SiN₂, making it more ionic with a more negative effective charge for N. Something similar may also apply for Li₈SiN₄ as it also has a small bandgap, but the crystal structure of Li₈SiN₄ has not fully been resolved in order to clarify this.

3. Conclusions

With increasing degree of condensation (Si/N ratio) in the nitridosilicates, the coordination number of N by Si increases, the Si-N bond lengths decrease, the M-N bond lengths increase and the bandgap increases as well. This can be understood by considering the changes in effective charge of N and Si-N bond lengths. With a low degree of condensation between the SiN₄ tetrahedra the N atom is under-bonded, giving it an effective negative charge. This effective charge becomes less negative with a higher degree of cross-linking between the SiN4 tetrahedra, making the M-N bonds weaker and longer. As a result of the less negative effective charge of N, the N 2p levels, and thus the top of the valence band, shift downwards and the bandgap becomes larger. The bandgap is also increased with increasing degree of condensation because the Si-N distance decreases, resulting in a larger splitting between the bonding (N) and antibonding (Si) orbitals. Some compounds, such as γ -Si₃N₄, SrSi₆N₈ and several Li containing compounds, show deviations to the general trends, which can be understood based on their differences in structure as compared to the other nitridosilicates, as their framework does not solely consist of cross-linking SiN4 tetrahedra.

The obtained insights on the relations between bandgap, structure and composition can be used when developing new materials with certain structural or optical properties. For example for the development of novel luminescent materials, for which the positions of the valence and conduction band are of direct influence on the photoluminescence properties.

Although we have focused ourselves in this manuscript on the nitridosilicates, the observed trends are expected to be more general and hold also for other series of compounds whose structure consists of a framework of cross-linked tetrahedra with larger counterions located in the cavities, such as the oxosilicates, oxoaluminates, nitridoaluminates and phosphates. Indeed, a decrease of the Si-O bond length with increasing Si/O ratio has been previously observed for the oxosilicates. 119-121 One can therefore expect that there might also be an increase of the bandgap and increase of the M-O bond length with increasing Si/O ratio. The smaller variation in Si/O ratio among the

oxosilicates *versus* the variation in Si/N ratio among the nitridosilicates may have hampered the establishment of such a relationship so far.

Conflicts of interest

There are no conflicts to declare.

Acknowledgements

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